



VANADIUM

SPUTTERING TARGET

Vanadium sputtering target shares properties with its source material. It is mainly used to produce specialty steel alloys such as high-speed tool steels. The most important industrial vanadium compound, vanadium pentoxide, is used as a catalyst for the production of sulfuric acid. The vanadium redox battery for energy storage may be an important application in the future.

Quick Facts

Product	:	Vanadium Sputtering Target
Stock No	:	NS6130-10-1367
CAS	:	7440-62-2
Backing Plate	:	(As per Customer requirement)

Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1367	99.99%	50.8 mm \pm 1mm	3 mm \pm 0.5mm

Technical Specification

Molecular Formula	Molecular Weight	Melting Point
V	163g/mol	1890°C



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High Purity
SPUTTERING
TARGET